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<b>INFORMATION DISCLOSURE STATEMENT BY APPLICANT</b>  <i>(use as many sheets as necessary)</i>				<b>APPLICATION NUMBER</b>	10/687,562
				<b>FILING DATE</b>	10/16/2003
				<b>FIRST NAMED INVENTOR</b>	Cherala et al.
				<b>Group Art Unit</b>	1763
				<b>Examiner Name</b>	Unassigned
<b>Sheet</b>	5	of	6	<b>Attorney Docket Number</b>	PA61-03-03

OTHER PRIOR ART - NON PATENT LITERATURE DOCUMENTS			
Examiner Initials*	Cite No.	Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, city and/or country where published.	T <sup>2</sup>

	C51	Chou, Nanoimprint Lithography and Lithographically Induced Self-Assembly, MRS Bulletin, pp. 512 - 517, 7/1/2001	
	C52	Choi et al., Design of Orientation Stages for Step and Flash Imprint Lithography, Precision Engineering, pp. 192 - 199, 1/1/2001	
	C53	Colburn et al., Step and Flash Imprint Lithography for sub-100 nm Patterning, Proceedings of SPIE Vol. 3997, pp. 453 - 457, 1/1/2000	
	C54	Chou et al., Imprint Lithography with Sub-10 nm Feature Size and High Throughput, Microelectronic Engineering 35, pp. 237 - 240, 1/1/1997	
	C55	Haisma et al., Mold-assisted Nanolithography: A Process for Reliable Pattern Replication, J. Vac. Sci. Technol. B, pp 4124 - 4128, 11/1/1996	
	C56	Johnson et al., Advances in Step and Flash Imprint Lithography, SPIE Microlithography Conference, 2/23/2003	
	C57	Colburn et al., Step and Flash Imprint Lithography: A New Approach to High-Resolution Patterning, Proc. Of SPIE, vol. 3676, 3/1/1999	
	C58	Heldari, Nanoimprint Lithography at the 6 in. Wafer Scale, J. Vac. Sci. Technol. B 18(6), pp. 3557 - 3560, 11/1/2000	
	C59	Translation of Japanese Patent 02-92603 Not available (no date)	

<b>Examiner Signature</b>		<b>Date Considered</b>	12-30-05
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\*Examiner: Initial if reference considered, whether or not citation is in conformance with MPEP 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

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